Special Topics on Basic EECS I
VLSI Devices
Lecture 8

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Homework#2

- Sheet resistivity
  - Assume the following electron distribution,

$$n(z) = n_s \exp\left(-\frac{z}{\Delta}\right),$$

  where the vertical coordinate, z, starts at 0.
  - Also assume a constant electron mobility, μ_n.
  - (Neglect holes.)
  - Calculate the sheet resistivity, which satisfies $R = \frac{L}{W}\rho_{sh}$.

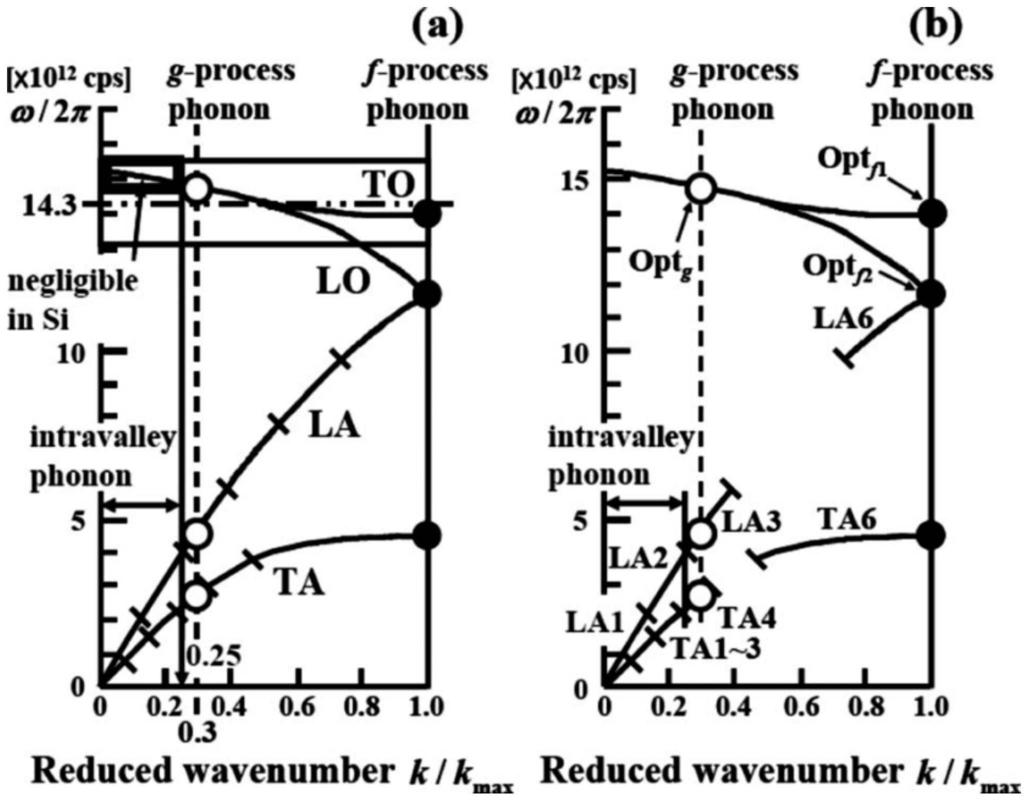
Example 2-2 of Hu's book

- Hole mobility, $\mu_p = 470\ \mathrm{cm^2V^{-1}s^{-1}}$
  - When the electric field is $10^3\ \mathrm{V\ cm^{-1}}$, the drift velocity is $4.7 \times 10^5\ \mathrm{cm\ s^{-1}}$.
  - Momentum relaxation time (with $m_p = 0.39\ m_0$) is 0.1 psec.

Phonon scattering

- Various phonon modes
  - Acoustic phonon : Low energy
  - Optical phonon : High energy, often treated as dispersion-less

~60 meV



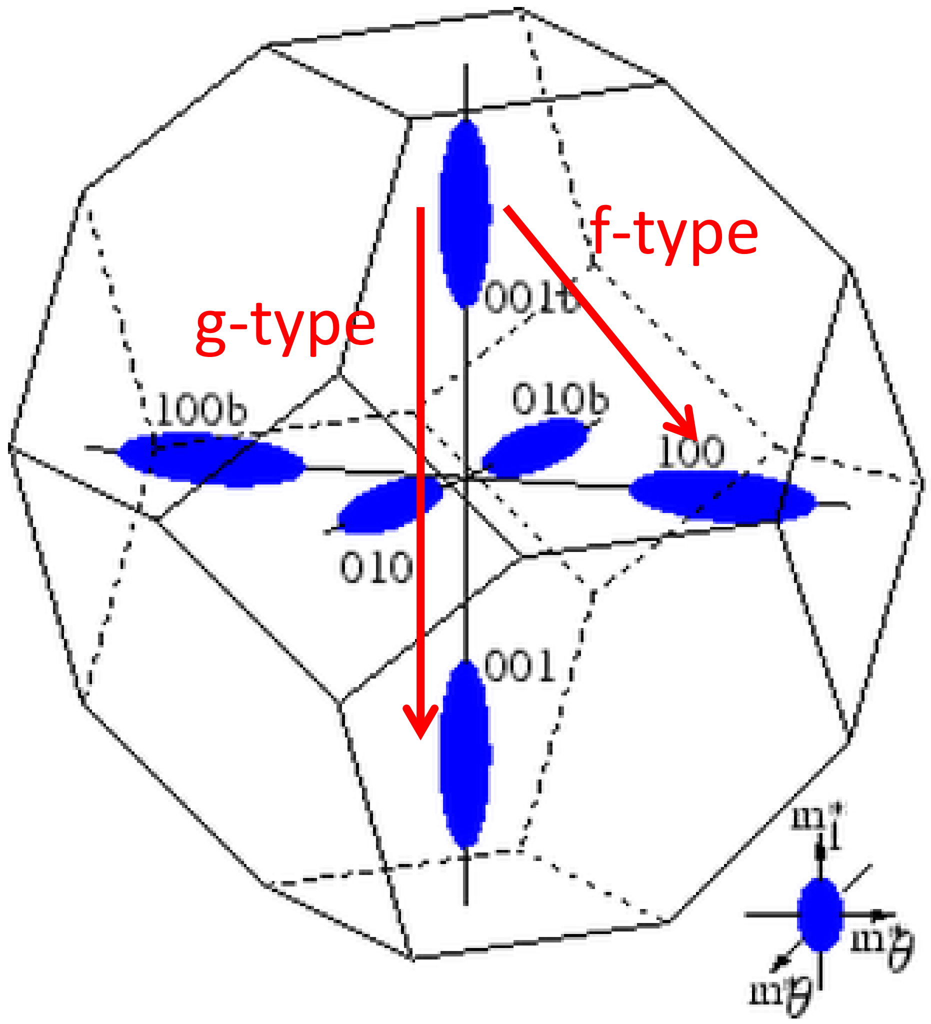
"Selection rule" matters. Intravalley / f-process / g-process

Typical parameters

- Various phonon modes
  - Acoustic phonon : Low energy

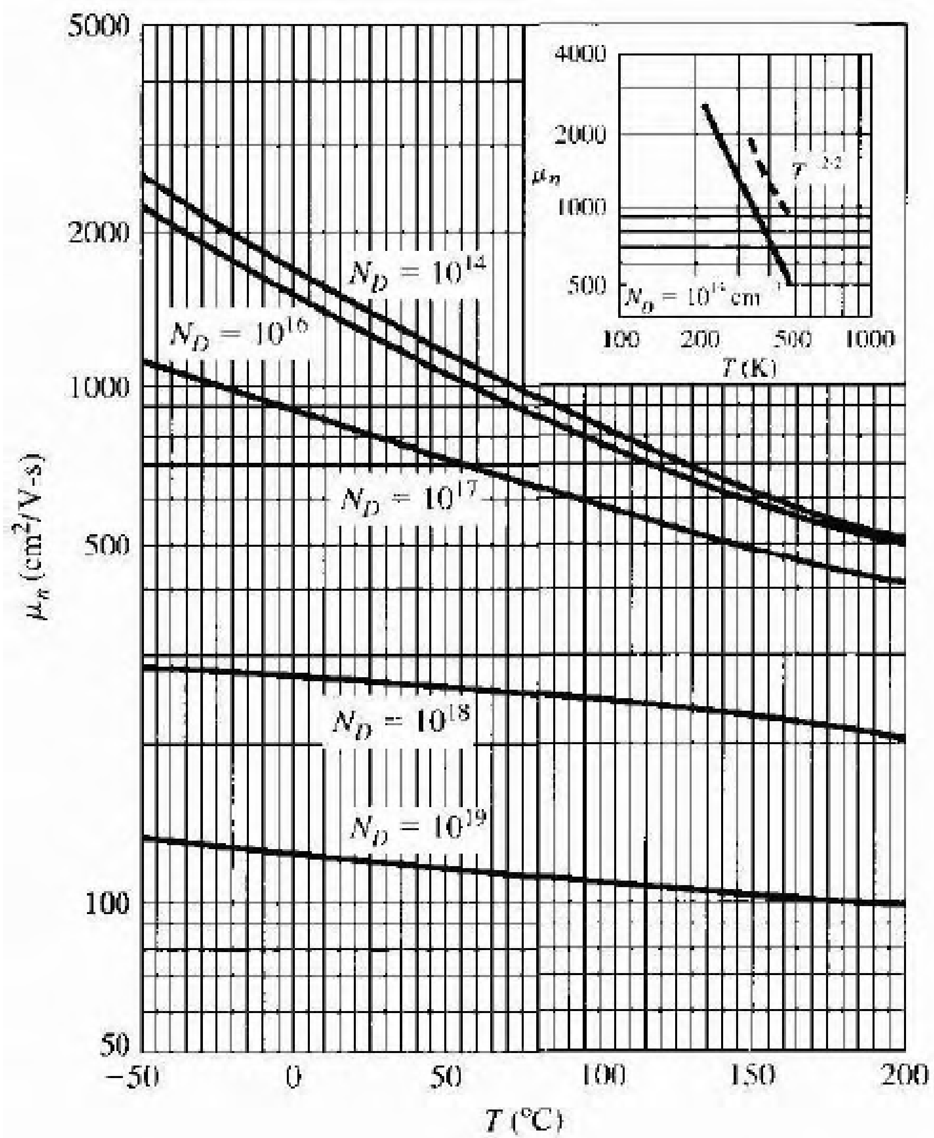
Mode	$D_t K$ (10^8 eV/cm)	$\hbar\omega$ (meV)	Type
TA	0.470	12.1	g-type
LA	0.740	18.5	g-type
LO	10.23	62.0	g-type
TA	0.280	19.0	f-type
LA	1.860	47.4	f-type
LO	1.860	58.6	f-type

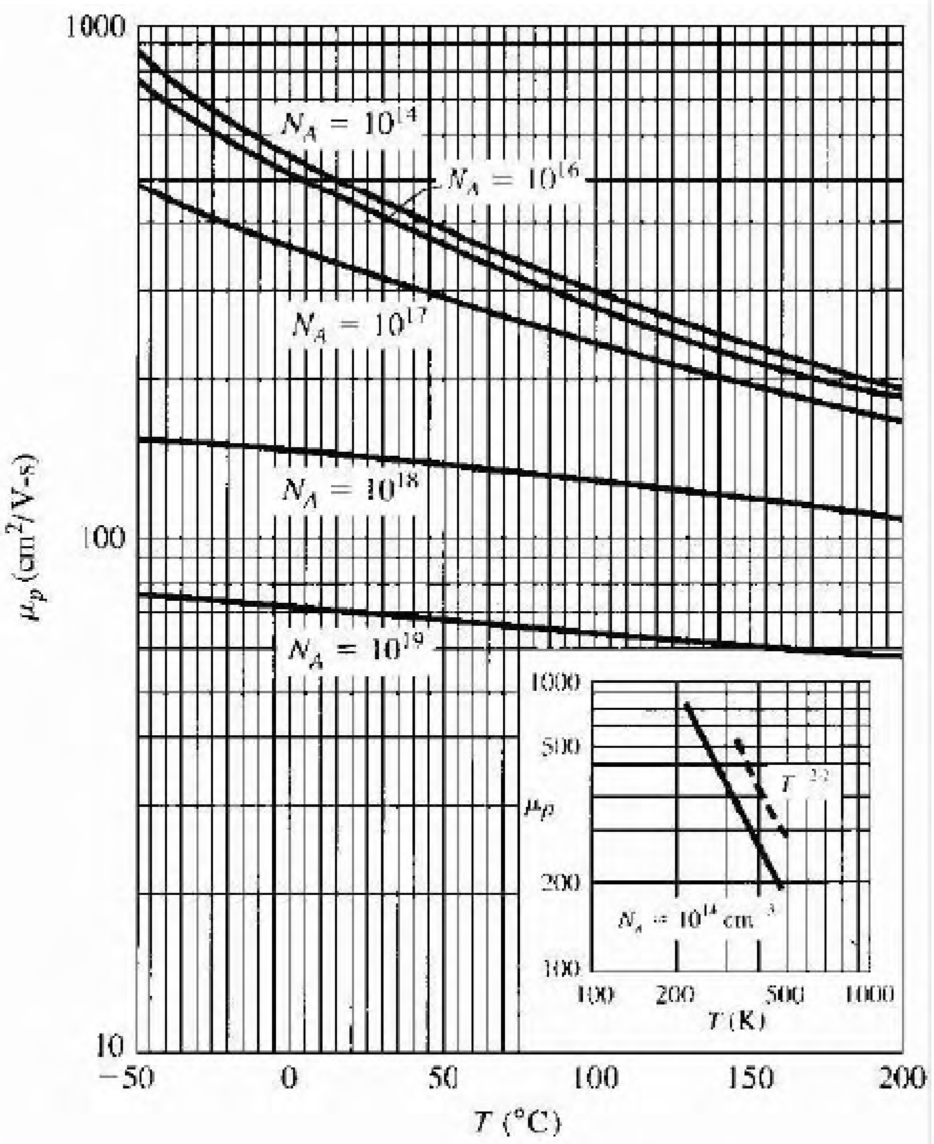
Parameters for inelastic phonon scatterings in the Si conduction band



Temperature & doping

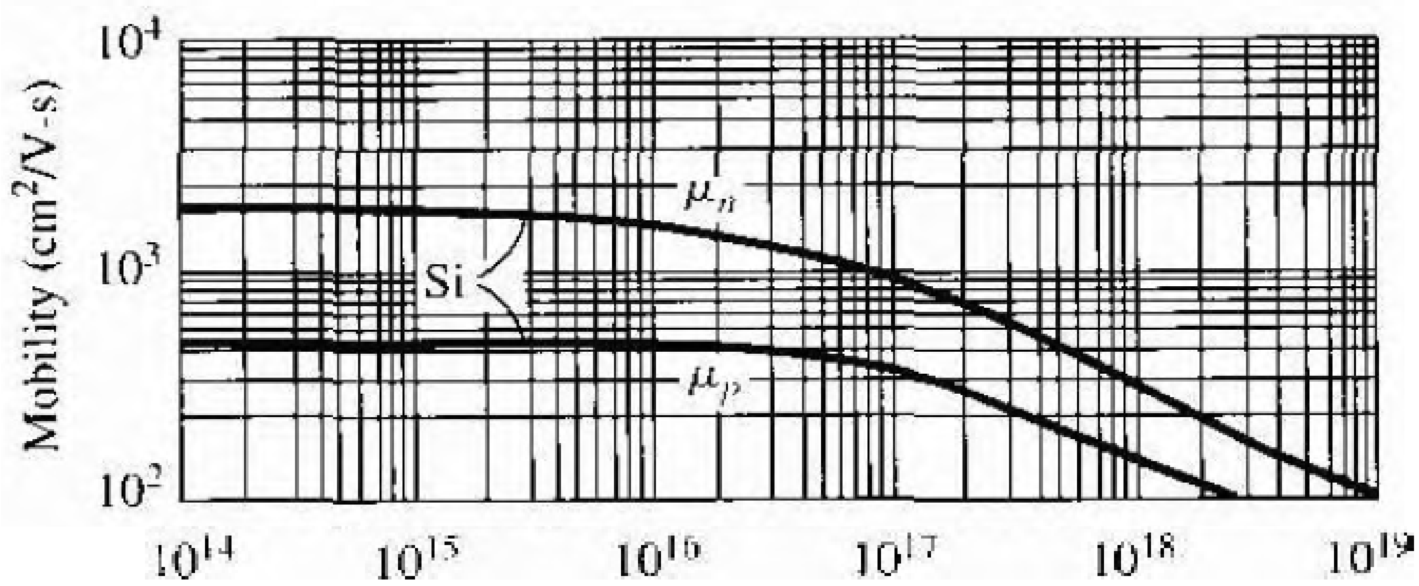
(Neamen's book)





Impurity concentration

- It is modeled as an elastic scattering process.



Impurity concentration (cm^{-3})

(Neamen's book)

- Which one is dominant? Phonon or impurity?
  - Matthiessen's rule, $\frac{1}{\mu} = \frac{1}{\mu_I} + \frac{1}{\mu_L}$

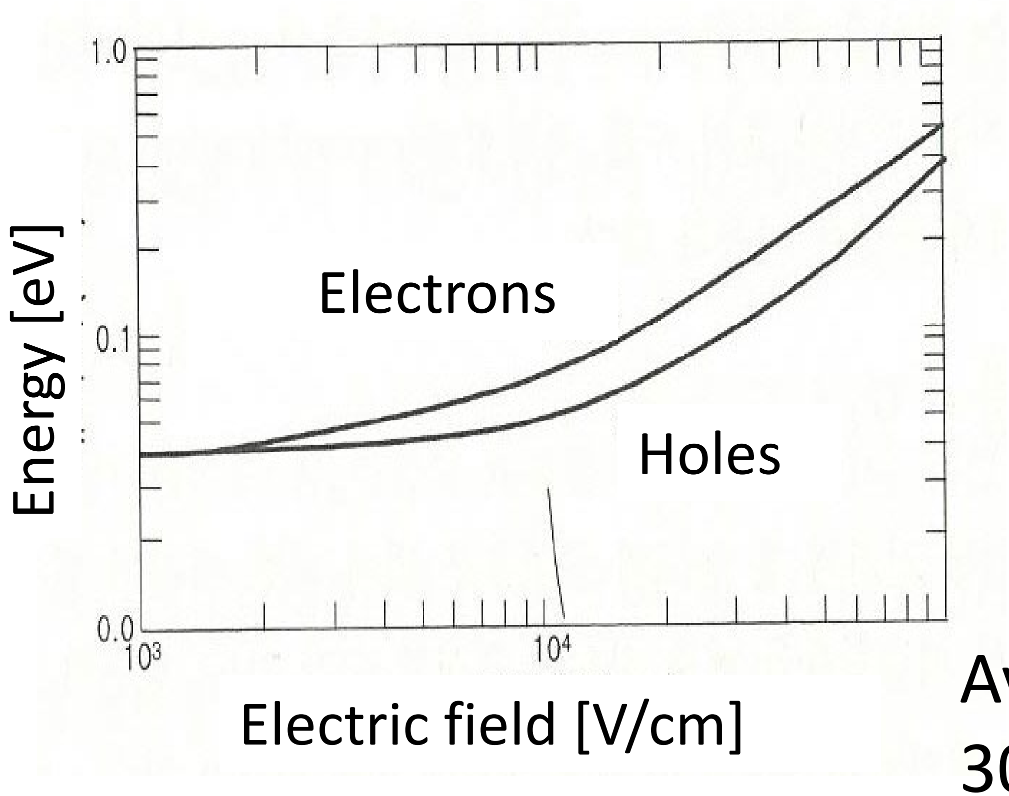
Taur, Eq. (2.27)

Matthiessen's rule

- When there are multiple contributions to the mobility,
  - (For example, phonon-limited mobility / impurity-limited mobility)
  - The overall collision rate is given by sum of all contributions.
  - $\frac{1}{\tau_m} = \frac{1}{\tau_{mL}} + \frac{1}{\tau_{mI}} + \cdots$
  - (The above relation holds exactly only in the microscopic level.)
  - When recalling $\mu = \frac{q\tau_m}{m_n}$, it means $\frac{1}{\mu_m} = \frac{1}{\mu_{mL}} + \frac{1}{\mu_{mI}} + \cdots$
  - It is very useful.

Hot electron

- Not only velocity, but also energy…
  - Increases when the electric field increases.
  - Increase of energy is a reason of the velocity saturation. *Why?*



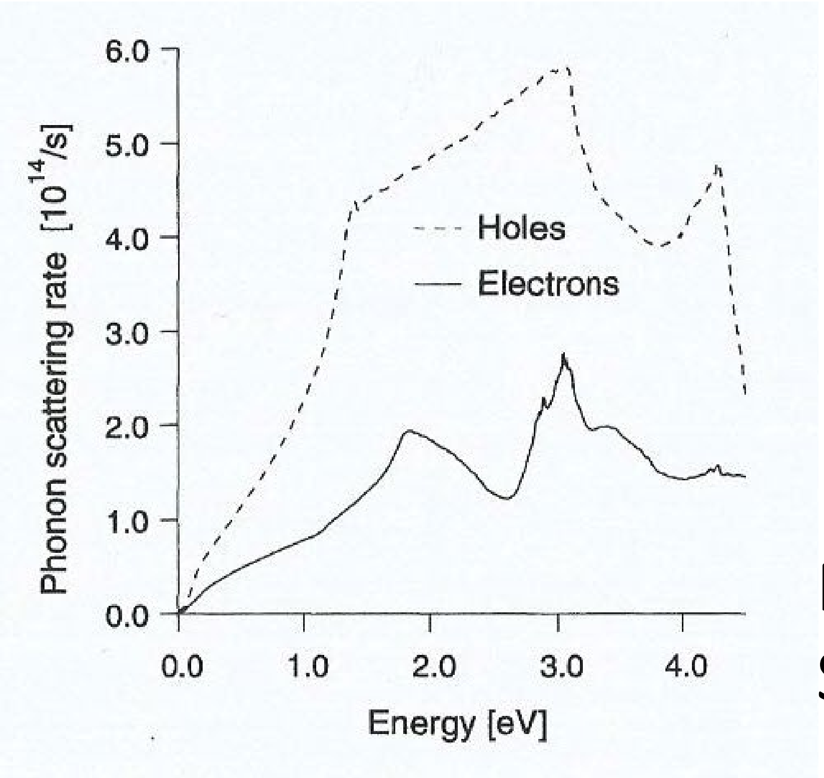
Up to 1 kV/cm, average energy is almost the same with the lattice energy.

Above 10 kV/cm, average energy significantly deviates from the lattice energy.

Average energy of electrons/holes in Si at 300K (Park's book)

Velocity saturation

- Electron with higher energy
  - Has a higher chance to be scattered by phonons. (Higher DOS)
  - More frequent scattering : Smaller τ_m

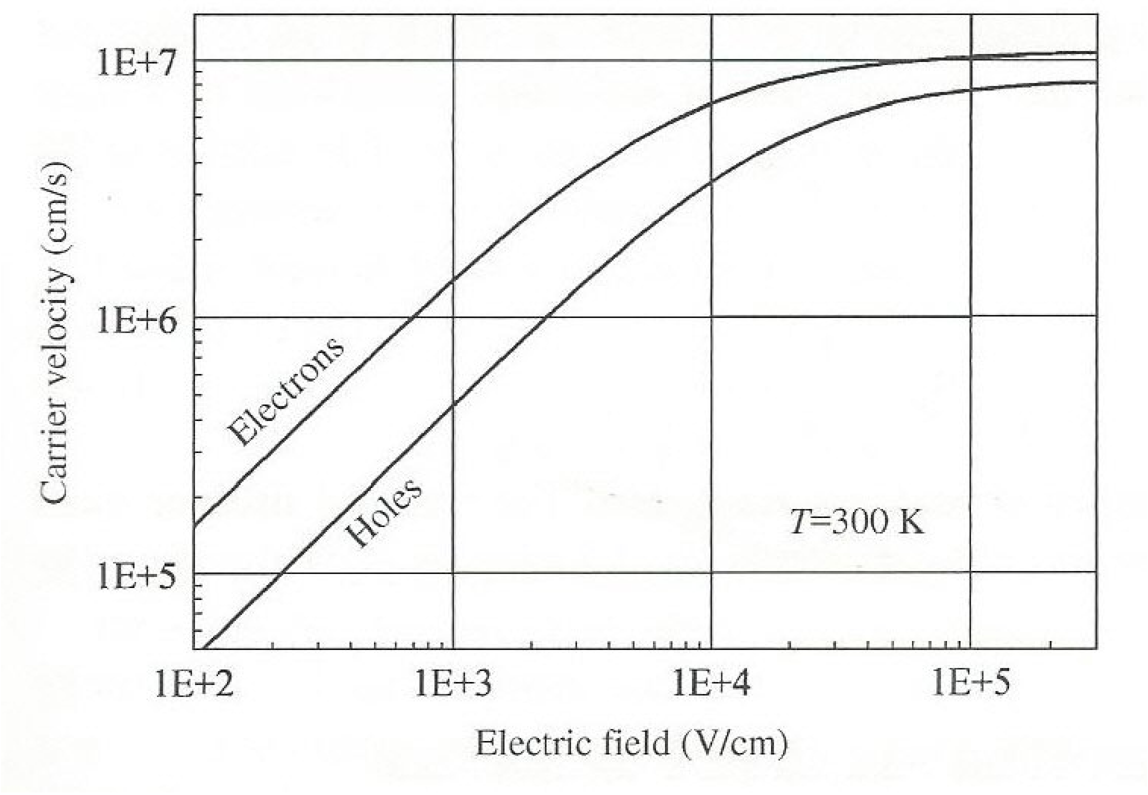


Phonon scattering rate in Si (Jungemann's book)

Phonon scattering rate in Si resembles the Density-Of-States.

Velocity vs. electric field

- At low electric fields, the linear relationship is valid.
  - At high electric fields, the velocity saturation starts to occur. The saturation velocity of Si is about 10^7 (cm/sec).



Velocity-field relationship in Si at 300K (Taur's book)

Caughey-Thomas relation

- For silicon,
  - Electron velocity can be approximated by

$$v_n = \frac{v_s}{\left[1 + \left(\frac{E_{on}}{E}\right)^2\right]^{0.5}}$$

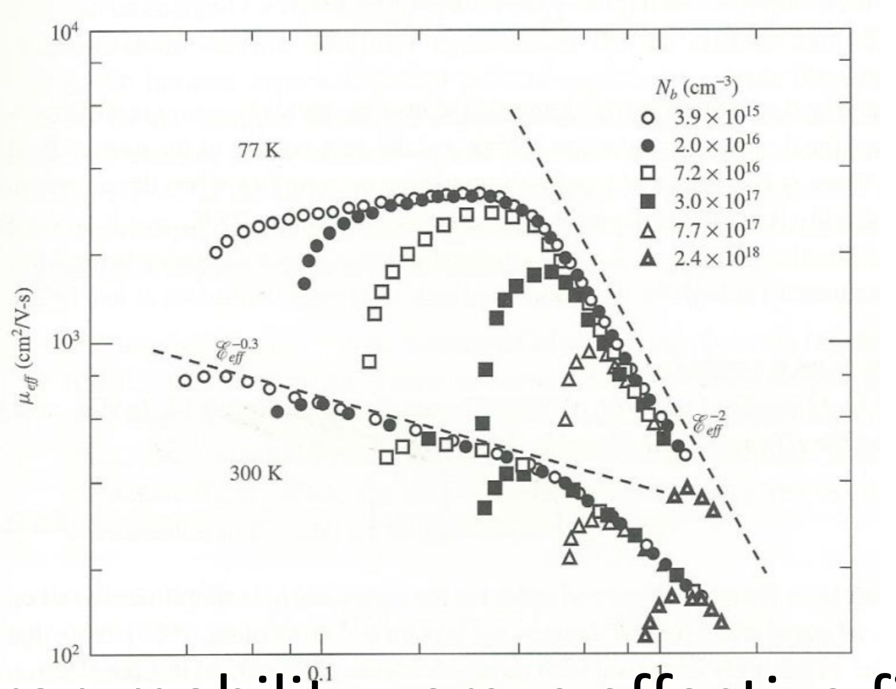
  - Hole velocity

$$v_p = \frac{v_s}{\left[1 + \left(\frac{E_{op}}{E}\right)\right]}$$

  - Why are they different?

Other scattering mechanisms

- We have discussed about the bulk mobility.
  - Other scattering mechanisms (alloy scattering & impact ionization)
  - Surface scattering severely reduces the inversion mobility.



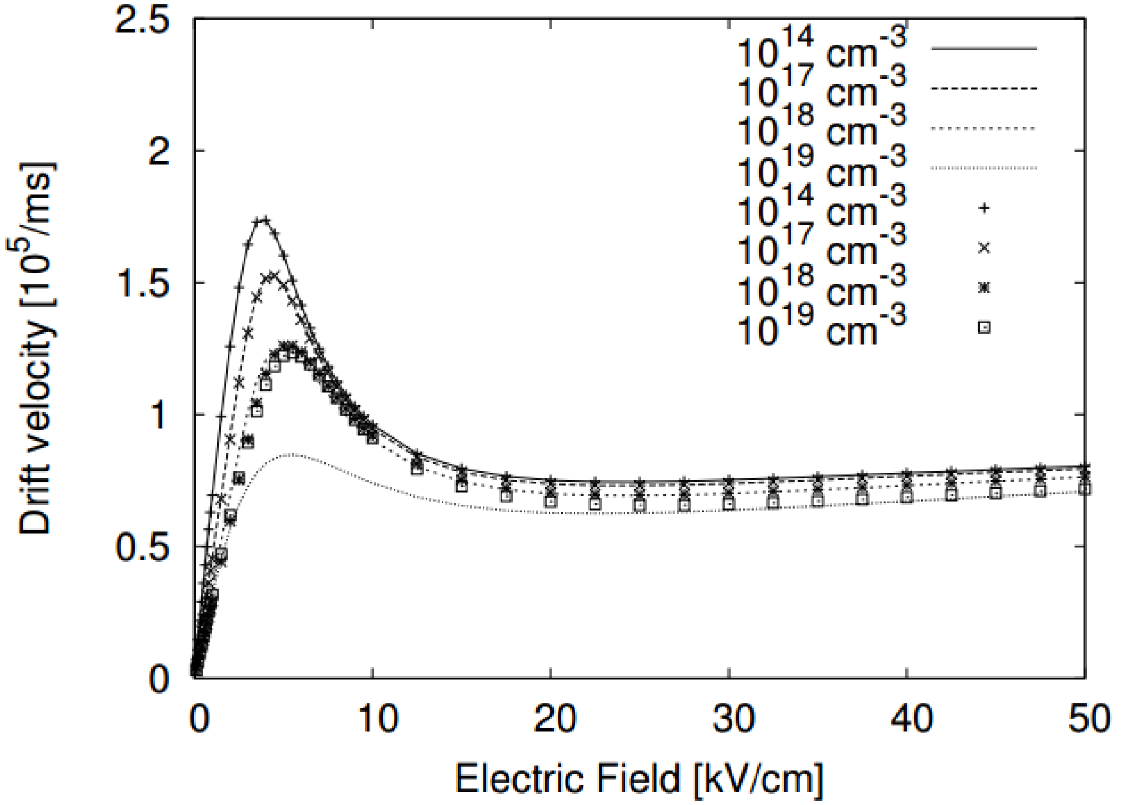
So-called "universal" mobility curve in the Si inversion layer.

Two difference contributions are clearly visible.

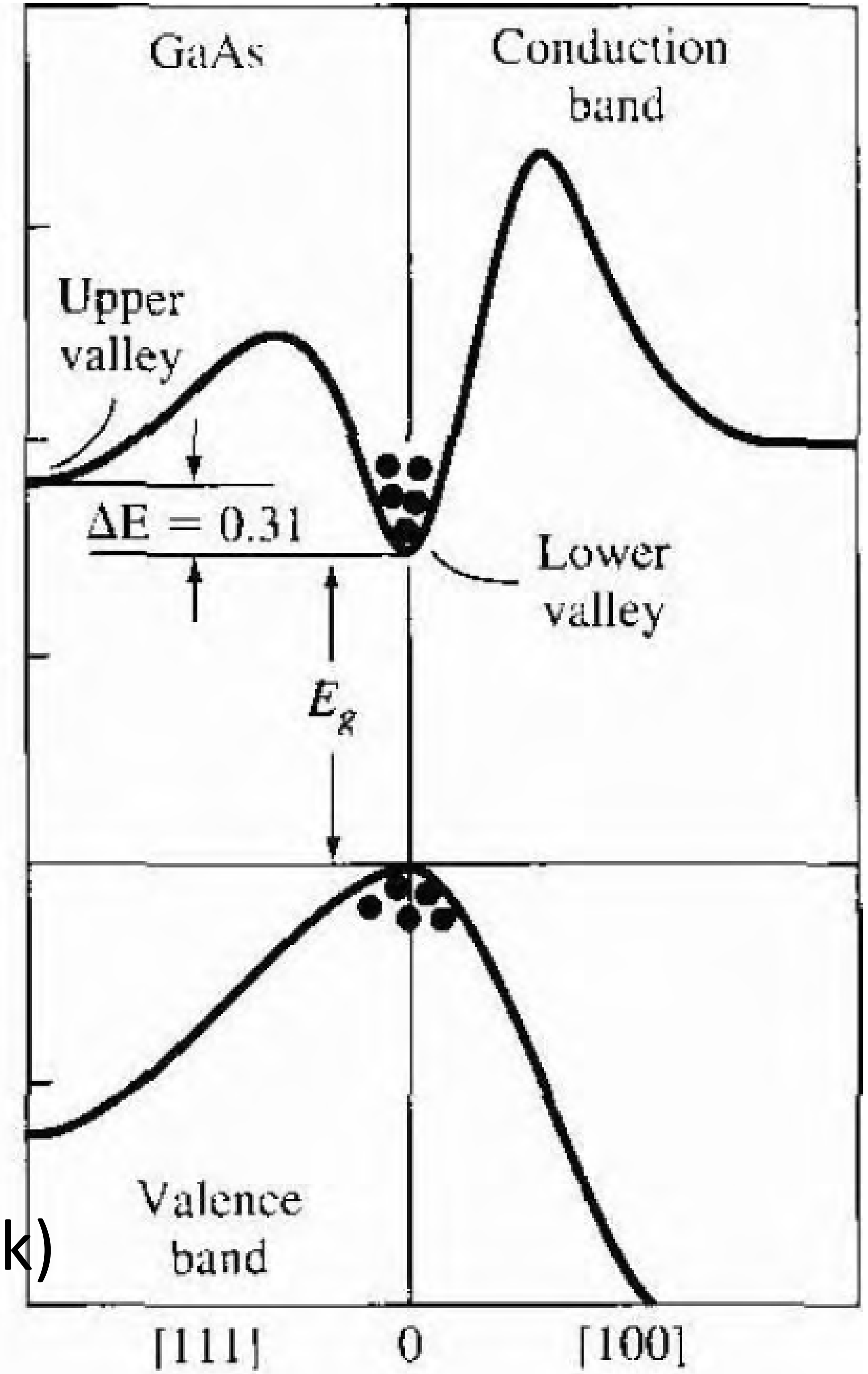
Electron mobility versus effective field for several doping concentrations (Takagi's paper)

GaAs case

- Negative differential mobility
  - Its *L* valley is heavy.



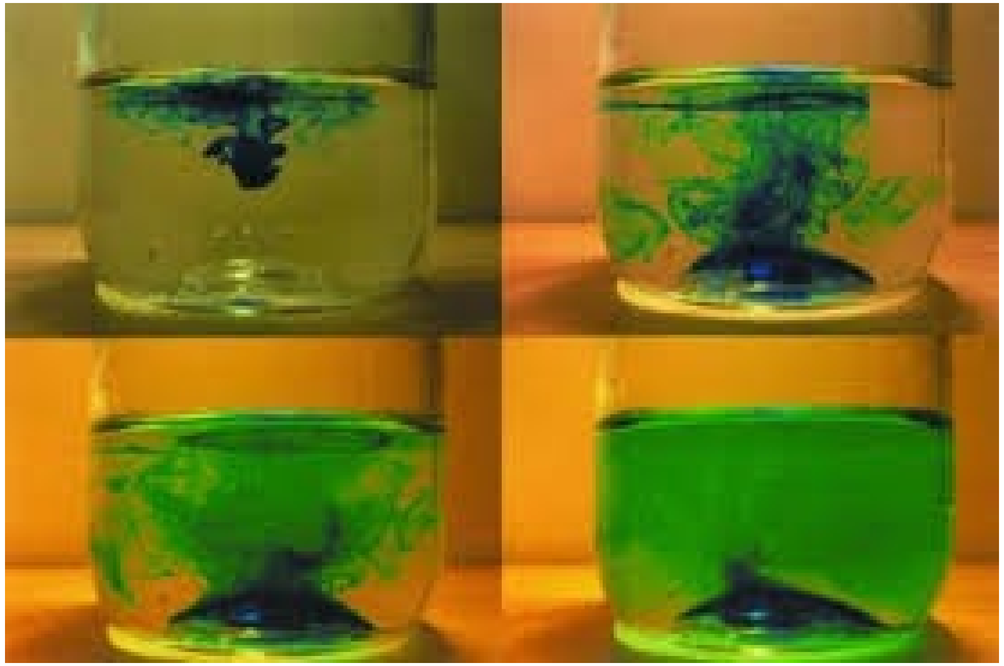
(J. Bieder et al., IWCE 2010)



(Neamen's book)

Diffusion

- It is not only for charged particles.
  - For example,



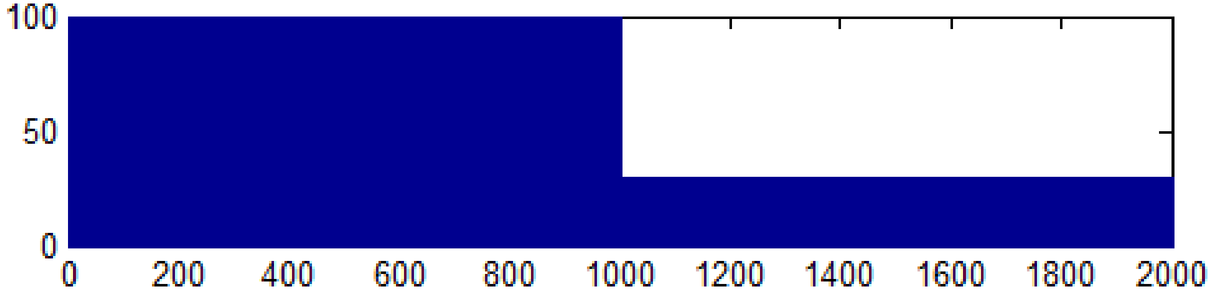
Diffusion of ink (Google images)

  - Therefore, no polarity is expected.

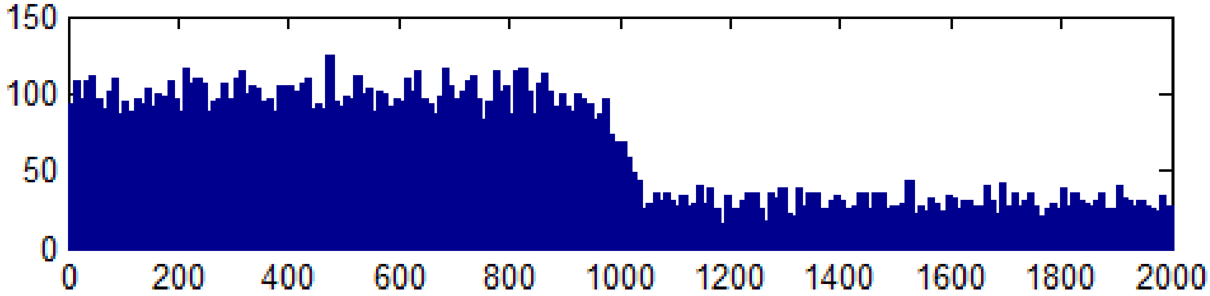
A simple game, again

- Random motion of balls in a 1D box
  - At each turn, they can move forward (+1) or backward (-1).

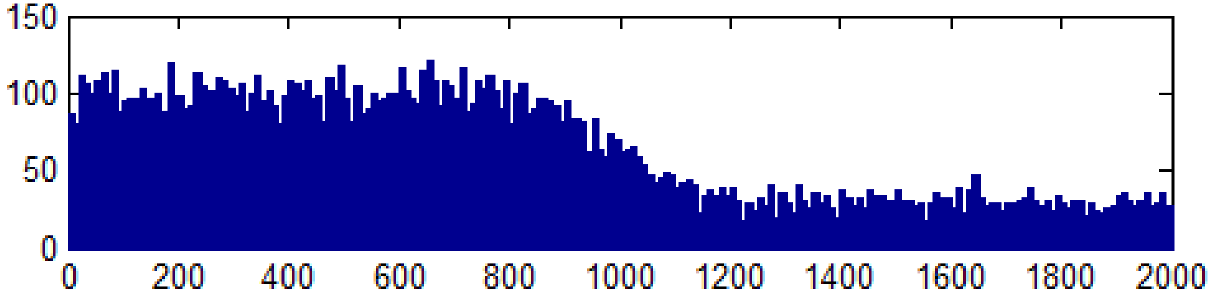
Initial condition



1 k turns



10 k turns



Equation

- Flux
  - The electron flux due to the diffusion mechanism is given by

$$\mathbf{F}_n = -D_n \nabla n$$

where D_n is the electron diffusion coefficient in the unit of (cm^2/sec).

  - The diffusion current density is

$$\mathbf{J}_{n,diff} = qD_n \nabla n \qquad \text{Taur, Eq. (2.36)}$$

- How about the hole?
  - The diffusion current density is

$$\mathbf{J}_{p,diff} = -qD_p \nabla p \qquad \text{Taur, Eq. (2.37)}$$

An example

- Taken from Neamen's book
  - Over 1 mm, the electron density varies linearly from 1X10^{18} cm^{-3} to 7X10^{17} cm^{-3}.
  - The diffusion coefficient is D_n = 225 cm2/sec.
  - Calculate the current density.

$$J_n = +qD_n \frac{dn}{dx}$$

$$= (1.6 \times 10^{-19}\ \mathrm{C})(225\ \mathrm{cm^2/s})\left(\frac{1 \times 10^{18}\ \mathrm{cm^{-3}} - 7 \times 10^{17}\ \mathrm{cm^{-3}}}{0.1\ \mathrm{cm}}\right)$$

$$= 108\ \mathrm{A/cm^2}$$

Revisit the total current density.

- Total current density
  - Electron current density

$$\mathbf{J}_n = q\mu_n n\mathbf{E} + qD_n \nabla n$$

Taur, Eq. (2.54)

  - Hole current density

$$\mathbf{J}_p = q\mu_p p\mathbf{E} - qD_p \nabla p$$

Taur, Eq. (2.55)

  - (Time-dependent) displacement current density

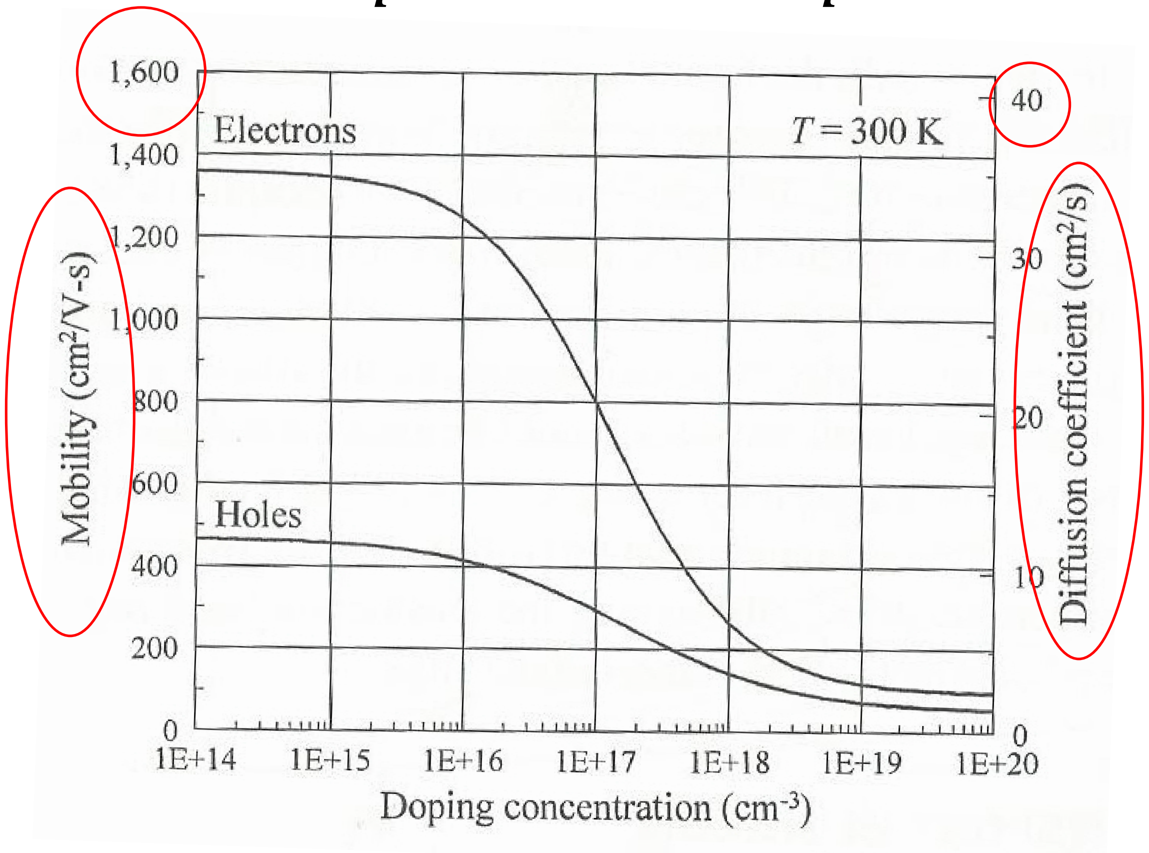
$$\mathbf{J}_{displacement} = \frac{\partial}{\partial t}(\epsilon \mathbf{E})$$

Einstein relation

- At equilibrium, we have the following relations:

$$D_n = \frac{k_B T}{q} \mu_n, D_p = \frac{k_B T}{q} \mu_p$$

Taur, Eq. (2.38) and Eq. (2.39)



(Park's book)

Thank you!